Lehrstuhl für
Elektronische Bauelemente

Advanced Thin Film Technologies

Dr. Detlef Theirich

WS 2025/2026

Information also on our website www.lfeb.uni-wuppertal.de

Starting date: **Tuesday 21.10.2025 at 2:15 p.m. in the seminar room FG-01.01**

Time / Place: Tuesday 2:15 – 5.45 pm, expected seminar room FG-01.01

These times can be adjusted on 14.10.2025 in agreement with the participants if necessary.

This lecture is aimed at:

Students of the **Master Smart Materials and System** in the specialization area Materials and Fundamentals

Students of the **Master Elektrotechnik** in the specialization area Polymer Electronics and Novel Technologies; area Materials and Processes.

Students of the **Master Wirtschaftsingenieurwesen Energiemanagement** in the compulsory elective area Energy Management 2; area Energy Systems and Components.

Students of the **Master Wirtschaftsingenieurwesen Informationstechnik** in the compulsory elective area of Electronics.

Students of the **Master Maschinenbau** in the compulsory elective area of Materials Science and Materials Engineering.

Content:

Introduction and repetition
Plasma
Selected deposition techniques (Sputtering, reactive sputtering, CVD and plasma CVD, ALD and plasma ALD)
Thin film properties and how these properties are effected by process parameters
Selected methods for thin film characterization
Industrial equipment and application examples

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